

Washington, DC 20425. Letters can also be sent via email to [bdelaviez@usccr.gov](mailto:bdelaviez@usccr.gov).

Send letters of interest for the Michigan Advisory Committee or Wisconsin Advisory Committees to: U.S. Commission on Civil Rights, Midwestern Regional Office, 55 W. Monroe St., Suite 410, Chicago, IL 60603. Letter can also be sent via email to [callen@usccr.gov](mailto:callen@usccr.gov).

Send letters of interest for the Texas Advisory Committee to: U.S. Commission on Civil Rights, Western Regional Office, 300 North Los Angeles St., Suite 2010, Los Angeles, CA 90012. Letter can also be sent via email to [atrevino@usccr.gov](mailto:atrevino@usccr.gov).

**FOR FURTHER INFORMATION CONTACT:**

David Mussatt, Chief, Regional Programs Unit, 55 W. Monroe St., Suite 410, Chicago, IL 60603, (312) 353-8311. Questions can also be directed via email to [dmussatt@usccr.gov](mailto:dmussatt@usccr.gov).

**SUPPLEMENTARY INFORMATION:** The Arkansas, Florida, Michigan, Massachusetts, Texas, and Wisconsin State Advisory Committees (SAC) are statutorily mandated advisory committees of the U.S. Commission on Civil Rights pursuant to 42 U.S.C. § 1975a. Under the charter for the SACs, the purpose is to provide advice and recommendations to the U.S. Commission on Civil Rights (Commission) on a broad range of civil rights matters in its respective state that pertain to alleged deprivations of voting rights or discrimination or denials of equal protection of the laws because of race, color, religion, sex, age, disability, or national origin, or the administration of justice. SACs also provide assistance to the Commission in its statutory obligation to serve as a national clearinghouse for civil rights information.

The SAC consists of not more than 19 members, each of whom will serve a two-year term. Members serve as unpaid Special Government Employees who are reimbursed for travel and expenses. To be eligible to be on a SAC, applicants must be residents of the respective state and have demonstrated expertise or interest in civil rights issues.

The Commission is an independent, bipartisan agency established by Congress in 1957 to focus on matters of race, color, religion, sex, age, disability, or national origin. Its mandate is to:

- Investigate complaints from citizens that their voting rights are being deprived,
- Study and collect information about discrimination or denials of equal protection under the law,
- Appraise federal civil rights laws and policies,

- Serve as a national clearinghouse on discrimination laws,
- Submit reports and findings and recommendations to the President and the Congress, and
- Issue public service announcements to discourage discrimination.

The Commission invites any individual who is eligible to be appointed a member of the Arkansas, Florida, Michigan, Massachusetts, Texas, or Wisconsin Advisory Committee covered by this notice to send a letter of interest and a resume to the respective address above.

Dated in Chicago, IL, on September 2, 2014.

**David Mussatt,**

*Chief, Regional Programs Unit.*

[FR Doc. 2014-21229 Filed 9-5-14; 8:45 am]

**BILLING CODE P**

**DEPARTMENT OF COMMERCE**

**Submission for OMB Review; Comment Request**

The Department of Commerce will submit to the Office of Management and Budget (OMB) for clearance the following proposal for collection of information under the provisions of the Paperwork Reduction Act (44 U.S.C. Chapter 35).

*Agency:* National Institute of Standards and Technology (NIST).

*Title:* Small Business Innovation Research (SBIR) Program Application Cover Sheet.

*OMB Control Number:* 0693-XXXX.

*Form Number(s):* N/A

*Type of Request:* Regular.

*Number of Respondents:* 100.

*Average Hours per Response:* 1 hour.

*Burden Hours:* 100.

*Needs and Uses:* The U.S. Small Business Administration (SBA) serves as the coordinating agency for the SBIR program. It directs the agency implementation of SBIR, reviews progress, and reports annually to Congress on its operation.

The information collected in the Cover Sheet provides identifying information and demographic data for use in NIST's annual report to the SBA on the program. The technical abstract is used in prevention of fraud, waste, and abuse by providing a method to compare similar applications to other agency SBIR programs. The abstract and potential commercial applications of successful applicants are posted on the agency Web site.

*Affected Public:* Business or other for-profit organizations.

*Frequency:* Annually.

*Respondent's Obligation:* Mandatory. This information collection request may be viewed at [reginfo.gov](http://reginfo.gov). Follow the instructions to view Department of Commerce collections currently under review by OMB.

Written comments and recommendations for the proposed information collection should be sent within 30 days of publication of this notice to [OIRA\\_Submission@omb.eop.gov](mailto:OIRA_Submission@omb.eop.gov) or fax to (202) 395-5806.

Dated: September 3, 2014.

**Gwellnar Banks,**

*Management Analyst, Office of the Chief Information Officer.*

[FR Doc. 2014-21300 Filed 9-5-14; 8:45 am]

**BILLING CODE 3510-13-P**

**DEPARTMENT OF COMMERCE**

**Foreign-Trade Zones Board**

[Order No. 1946]

**Reorganization of Foreign-Trade Zone 62 Under Alternative Site Framework Brownsville, Texas**

Pursuant to its authority under the Foreign-Trade Zones Act of June 18, 1934, as amended (19 U.S.C. 81a-81u), the Foreign-Trade Zones Board (the Board) adopts the following Order:

*Whereas*, the Board adopted the alternative site framework (ASF) (15 CFR Sec. 400.2(c)) as an option for the establishment or reorganization of zones;

*Whereas*, the Brownsville Navigation District, grantee of Foreign-Trade Zone 62, submitted an application to the Board (FTZ Docket B-103-2013, docketed 12-04-2013) for authority to reorganize under the ASF with a service area of Cameron County, Texas, within and adjacent to the Brownsville Customs and Border Protection port of entry, to renumber a 71-acre portion of Site 1 as Site 5, and to categorize FTZ 62's existing Sites 1, 2, 3, 4 and 5 as magnet sites;

*Whereas*, notice inviting public comment was given in the **Federal Register** (78 FR 73823, 12-09-2013) and the application has been processed pursuant to the FTZ Act and the Board's regulations; and,

*Whereas*, the Board adopts the findings and recommendations of the examiner's report, and finds that the requirements of the FTZ Act and the Board's regulations are satisfied;

*Now, therefore*, the Board hereby orders:

The application to reorganize FTZ 62 under the ASF is approved, subject to the FTZ Act and the Board's regulations,

including Section 400.13, to the Board's standard 2,000-acre activation limit for the zone, and to a five-year ASF sunset provision for magnet sites that would terminate authority for Sites 2, 3, 4 and 5 if not activated by August 31, 2019.

Signed at Washington, DC, this 29th day of August 2014.

**Paul Piquado,**

*Assistant Secretary of Commerce for Enforcement and Compliance, Alternate Chairman, Foreign-Trade Zones Board.*

[FR Doc. 2014-21331 Filed 9-5-14; 8:45 am]

**BILLING CODE 3510-DS-P**

## DEPARTMENT OF COMMERCE

### Bureau of Industry and Security

[Docket No. 140814669-4669-01]

#### Notice of Foreign Availability Assessment: Anisotropic Plasma Dry Etching Equipment

**AGENCY:** Bureau of Industry and Security, Department of Commerce.

**ACTION:** Notice of Initiation of a Foreign Availability Assessment and Request for Comments.

**SUMMARY:** This notice is to announce that the Bureau of Industry and Security (BIS) is initiating a foreign availability assessment pursuant to section 5(f) of the Export Administration Act of 1979, as amended (EAA). BIS's Office of Technology Evaluation (OTE) will oversee the assessment of the foreign availability in China of anisotropic plasma dry etching equipment. BIS is also seeking public comments on the foreign availability of this equipment in China.

**DATES:** Comments must be received by September 23, 2014.

**ADDRESSES:** You may submit comments by any of the following methods:

- Email: [EtchComments@bis.doc.gov](mailto:EtchComments@bis.doc.gov). Include the phrase "Plasma Dry Etch FA Study" in the subject line;

- On paper to Orestes Theocharides, Office of Technology Evaluation, Bureau of Industry and Security, U.S. Department of Commerce, Room 1093, 1401 Constitution Avenue NW., Washington, DC 20230, or his email at [orestes.theocharides@bis.doc.gov](mailto:orestes.theocharides@bis.doc.gov). Include the phrase "Plasma Dry Etch FA Study"; or

- Fax to (202) 482-5361. Include the phrase "Plasma Dry Etch FA Study".

**FOR FURTHER INFORMATION CONTACT:**

Gerard Horner, Director, Office of Technology Evaluation, Bureau of Industry and Security, Department of Commerce, Washington, DC 20230, Telephone: (202) 482-2078; email: [gerard.horner@bis.doc.gov](mailto:gerard.horner@bis.doc.gov).

#### SUPPLEMENTARY INFORMATION:

##### Background

Section 5(f) of the Export Administration Act of 1979, as amended (EAA), authorizes the Secretary of Commerce to conduct foreign availability assessments to examine and reevaluate the effectiveness of U.S. dual-use export controls on certain items that are controlled for national security reasons under the Export Administration Regulations (EAR). The Bureau of Industry and Security (BIS) has been delegated the responsibility of conducting these assessments and compiling a final report for the Secretary's review and consideration when issuing a final foreign availability determination. Part 768 of the EAR sets forth the procedures related to foreign availability assessments. BIS is publishing this notice to announce the initiation of an assessment and to request public comments on certain aspects of the item under review.

##### Foreign Availability Assessment

On behalf of the Secretary, BIS has initiated an assessment in response to a foreign availability claim received from the Semiconductor Equipment and Materials International (SEMI) industry association. The SEMI claim asserts the foreign availability of anisotropic plasma dry etching equipment in China from Chinese sources. The etching equipment in China is allegedly designed or optimized to produce critical dimensions of 65 nm or less; *and* within-wafer non-uniformity equal to or less than 10%  $3\sigma$  measured with an edge exclusion of 2 mm or less.

Items with these capabilities are currently controlled in the U.S. for national security reasons under Export Control Commodity Classification Number (ECCN) 3B001.c on the Commerce Control List (Supplement No. 1 to Part 774 of the EAR). U.S. controls do not allow this item to be exported to China without a license. This type of semiconductor etching equipment is used in the production process of a variety of dual-use semiconductor devices such as flash memories, microwave monolithic integrated circuits, transistors, and analog-to-digital-converters. These devices are suitable for use in a variety of both civil and military applications that include different types of radars, point-to-point radio communications, microprocessors, cellular infrastructure, and satellite communications.

The SEMI claim asserts that anisotropic plasma dry etch equipment of comparable quality to those subject to control under 3B001.c are available-in-

fact from Chinese sources in sufficient quantities to render the U.S. export control of the etch equipment ineffective.

BIS has reviewed the SEMI claim and determined that it has sufficient evidence to assess whether or not foreign availability of this etch equipment from Chinese sources exists. Therefore, BIS is initiating a foreign availability assessment of anisotropic plasma dry etching equipment designed or optimized to produce critical dimensions of 65 nm or less; *and* within-wafer non-uniformity equal to or less than 10%  $3\sigma$  measured with an edge exclusion of 2 mm or less. Upon completion of the assessment, BIS will submit its findings to the Secretary of Commerce, who in turn will issue a final determination for the Department. The final determination will be published in the **Federal Register**.

##### Request for Comments

To assist in assessing the foreign availability, described above, of this anisotropic plasma dry etch equipment, BIS is seeking public comments and submissions that relate to the following information:

- Product names and model designations of anisotropic plasma dry etch equipment that are made in China and that are comparable to the U.S. anisotropic plasma dry etch equipment designed or optimized to produce critical dimensions of 65 nm or less; *and* within-wafer non-uniformity equal to or less than 10%  $3\sigma$  measured with an edge exclusion of 2 mm or less. (U.S. dry etch equipment);
- names and locations of Chinese companies that produce and export indigenously-produced anisotropic plasma dry etch equipment comparable to U.S. dry etch equipment;
- Chinese production quantities, sales, and/or exports of anisotropic plasma dry etch equipment comparable to U.S. dry etch equipment;
- data on U.S. imports of Chinese anisotropic plasma dry etch equipment comparable to U.S. dry etch equipment, and/or testing and analysis of such dry etch equipment;
- estimates of the economic impact on U.S. companies of the export controls on the U.S. dry etch equipment.

Any tangible evidence to support the above information would also be useful to BIS in its conduct of this assessment. Examples of other useful evidence are found in Supplement No. 1 to Part 768 of the EAR.

##### Submission of Comments

All comments may be submitted by any of the methods indicated in this